In the claims:

1. (Original) A sputtering target material, wherein a portion to be used for sputtering of the sputtering target material is subjected to a friction stir processing.

2. (Original) The sputtering target material according to claim 1, wherein the sputtering target material is made of an aluminum alloy.

3. (Original) The sputtering target material according to claim 2, wherein the aluminum alloy comprises carbon.

4. (Currently Amended) The sputtering target material according to claim 2 ~~or 3~~, comprising any one or more elements selected from nickel, cobalt and iron.

5. (Currently Amended) The sputtering target material according to ~~any one of claims 1 to 4~~ claim 1, wherein the sputtering target material is a sintered material or a cast material.

6. (New) The sputtering target material according to claim 3, comprising any one or more elements selected from nickel, cobalt and iron.

7. (New) The sputtering target material according to claim 2, wherein the sputtering target material is a sintered material or a cast material.

8. (New) The sputtering target material according to claim 3, wherein the sputtering target material is a sintered material or a cast material.

9. (New) The sputtering target material according to claim 4, wherein the sputtering target material is a sintered material or a cast material.

10. (New) The sputtering target material according to claim 6, wherein the sputtering target material is a sintered material or a cast material.

11. (New) A method for processing a sputtering target material which comprises subjecting a portion of a sputtering target material to a friction stir processing.

12. (New) The method according to claim 11, wherein the sputtering target material is made of an aluminum alloy.

13. (New) The method according to claim 12, wherein the aluminum alloy comprises carbon.

14. (New) The method according to claim 12, comprising any one or more elements selected from nickel, cobalt and iron.

15. (New) The method according to claim 11, wherein the sputtering target material is a sintered material or a cast material.

16. (New) The method according to claim 13, comprising any one or more elements selected from nickel, cobalt and iron.

17. (New) The method according to claim 12, wherein the sputtering target material is a sintered material or a cast material.

18. (New) The method according to claim 13, wherein the sputtering target material is a sintered material or a cast material.

19. (New) The method according to claim 14, wherein the sputtering target material is a

sintered material or a cast material.

20. (New) A method for suppressing arcing and splashing between a sputtering apparatus and a sputtering target material which comprises previously subjecting the sputtering target material to a friction stir processing.